Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	168	427/248.1.ccls. and (mask shield shadow) and angle	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:54
S2	22	427/248.1.ccls. and (mask shield shadow) and angle and oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:45
S3	11	(pelhos klemmer seigler).in. and oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:47
S4	40	427/248.1.ccls. and (mask shield shadow) with angle	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:57
S5	20	427/2$.ccls. and (mask shield shadow) with angle with oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:59
S6	29	427/2$.ccls. and (mask shield shadow) and angle with oblique and rotate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:05
S7	4	427/2$.ccls. and (mask shield shadow) and nozzle with (askew diagonal aslant asymmetrical angled oblique) and rotate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:07
S8	17	427/2$.ccls. and (mask shield shadow) and vapor$5 with (askew diagonal aslant asymmetrical angled oblique) and rotate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:09
S9	52	427/2$.ccls. and (mask shield shadow) and vapor$5 with (askew diagonal aslant asymmetrical angled oblique)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:14
S10	1	disc and (mask shield shadow) with vapor$5 with (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:16
S11	1	substrate and (mask shield shadow) with vapor$5 with (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:16
S12	4	substrate and (mask shield shadow) with vapor$5 and (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:35

S13	2	substrate with vapor$5 with (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:24
S14	29	118/720,721.ccls. and oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:27
S15	31	118/720,721.ccls. and (disc disk wafer) with (pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:30
S16	90	118/720,721.ccls. and 118/730.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:32
S17	0	118/720,721.ccls. and 118/730.ccls. and radial adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:32
S18	13	118/720,721.ccls. and 118/730.ccls. and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:32
S19	26	(disc disk wafer) and (mask shield shadow) with vapor$5 with (circumferential azimuthal radial)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:55
S21	2	(disc disk wafer) and (mask shield shadow) with vapor$5 with control$4 near3 pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 10:56
S22	13	(disc disk wafer) and (mask shield shadow) with vapor$5 with control$4 with pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 17:00
S23	6	(("5198090") or ("5804046") or ("20030019745")).PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/04/20 08:56
S25	534	(disc disk wafer) and (mask shield shadow) with vapor$5 with pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 10:56
S26	1	(disc disk wafer) and (mask shield shadow) with vapor$5 with pattern with radial	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 10:56